

Abstract of the Disclosure

An object of the present invention is to stably supply
a treatment chamber with a treatment gas with a
5 prescribed composition. A spin on dielectric (SOD)
system includes a film treatment apparatus of the
present invention which comprises, for forming an
interlayer insulating film, a treatment chamber for
placing a wafer W, a first mass flow controller for NH_3
10 gas, a second mass flow controller for N_2 gas with a
prescribed water vapor, thereby supplying the treatment
chamber with a gas of a prescribed composition.